

Program

The 4th International Conference on PLASMA NanoTechnology & Science (IC-PLANTS 2011)

Thursday, March 10, 2011

14	00	Registration	
	00	Opening Remarks	
15	05	I-1	Pascal Chabert (LPP Ecole Polytechnique, France) <i>Global Model of Micro Hollow Cathode Discharges in Argon</i>
	45	I-2	Roderick W. Boswell (Australian National University, Australia) <i>Plasma Propagation of a 13.56 MHz Asymmetric Surface Barrier Discharge in Atmospheric Pressure Air</i>
16	25	Break	
	45	O-1	Ho-Jun Lee, Hae June Lee (Pusan National University, Korea) <i>Weakly Magnetized Inductively Coupled Plasma Source for 450 mm Wafer Processing Tool</i>
17	05	O-2	Ivan P. Ganachev, H. Sugai (Shibaura Mechatronics Corporation, Chubu University, Japan) <i>Optimal Aspect Ratio for Multi-hollow Microwave Discharge</i>
	25	I-3	Masaru Hori (Nagoya University, Japan) <i>High Speed Surface Modification with AC Excited Ultra High Density Non-Equilibrium Atmospheric Pressure Plasma</i>
18	05	*The bus for the banquet site will leave at 18:40 in front of the conference hall.	
Banquet (19:00 ~ 21:00)			

Friday, March 11, 2011

8	45	Registration	
9	20	I-4	Jürgen Röpecke (Leibniz Institute for Plasma Science and Technology (INP Greifswald), Germany) <i>Applications of MIR-Laser Absorption Techniques for Plasma Diagnostics in Basic Research and Industry</i>
10	00	I-5	Seiichi Miyazaki (Nagoya University, Japan) <i>Application of Remote Hydrogen Plasma to Selective Processing for Ge-based Devices - Crystallization, Etching and Metallization</i>
	40	Break	
	00	O-3	J-P Booth, E. V. Johnson, P-A. Delattre, T. Verbeke, and J-C Vanel (LPP Ecole Polytechnique, France) <i>RF Waveform Tailoring to Control Film Morphology during Nanocrystalline Silicon PECVD</i>
11	20	O-4	R.V. Bekarevich, S. Miura, Di Lu, A. Ogino, M. Nagatsu (Shizuoka University, Japan) <i>Effect of Ion Biasing Energy on Growth of Carbon Nanomaterials at Low Substrate Temperature Using Microwave Plasma CVD</i>
	40	O-5	M. Shiratani, N. Itagaki, K. Kuwahara, K. Nakahara, D. Yamashita, G. Uchida, K. Kamataki, K. Koga (Kyushu University, Japan) <i>Ultra Low Resistive NM Thick AZO Films Deposited by Magnetron Sputtering Using Solid Phase Crystallization</i>
12	00	O-6	A. Hikita, T. Iwamoto, S. Kumagai, M. Sasaki (Toyota Technological Institute, Japan) <i>Light-Weighted Micromirror Fabricated Using Stacked Photoresist Masks Realized by UV Curing</i>
13	20	Lunch	
14	00	I-6	Klaus Bartschat (Drake University, USA) <i>Benchmark Calculations of Atomic Data for Plasma Applications</i>
	40	I-7	Zoran Lj. Petrović (University of Belgrade, Serbia) <i>New phenomenology in description of Townsend discharges and gas breakdown: from standard size to micro discharges</i>
15	20	O-7	H. Tsuda, Y. Takao, K. Eriguchi, K. Ono (Kyoto University, Japan) <i>Surface Roughness Formation during Si Etching in Cl₂ and Cl₂/O₂ plasmas: Atomic-scale Analysis of Three-dimensional Feature Profile Evolution</i>
	40	Break	
Poster Session (16:00 ~ 18:00)			

Saturday, March 12, 2011

8	45	Registration	
9	00	I-8	William G. Graham (Queen's University Belfast, UK) <i>The Physics and Chemistry of Plasmas in and onto Liquids</i>
	40	I-9	Toshiro Kaneko (Tohoku University, Japan) <i>Generation of Controlled Gas-Liquid Interfacial Plasmas for Synthesis of Novel Nano-BioConjugates</i>
	20	Break	
10	35	O-8	F. Odeyemi, A. Rabinovich, A. Fridman (Drexel University, USA) <i>Non Equilibrium Plasma Conversion of Pyrogas into Synthesis Gas</i>
	55	O-9	T. Hagino, H. Kano, K. Ishikawa, K. Takeda, H. Kondo, M. Sekine, M. Hori (Nagoya University, Japan) <i>Synthesis of Nano-graphene by Plasma in Liquid Ethanol</i>
11	15	I-10	Michael Kong (Loughborough University, UK) <i>Plasma Treatment of Living Tissues – How Penetrating are the Plasma-mediated Therapeutic Effects</i>
	55	Closing Remarks	
Excursion			
(Departure from the conference site ~12:15, Return to Takayama station ~16:30)			

Invited talk : 30 min presentation, 10 min discussions,
Contributed talk : 15 min presentation, 5 min discussions